

Remarks

The following request for reconsideration is made in response to the Office Action mailed November 15, 2007. Claims 1-14 and 20-29 are pending in the application.

Applicants' attorney would like to thank the Examiner for the telephone interview held on December 28, 2007. During the interview claims 1 and 5 were discussed along with U.S. Patent No. 6,544,699 to Kim et al. cited by the Examiner. In particular, it was discussed that the '699 patent did not disclose the claimed combination including producing a revised set of mask/reticle data that are compensated for etch effects that is used as a target layer for OPC as set forth in Claim 1. In addition, the '699 patent does not disclose the claimed combination including applying etch biases calculated from an initial set of mask/reticle data within an OPC loop. During the interview the Examiner indicated that the anticipation rejection in view of the '699 patent to Kim et al. would be withdrawn.

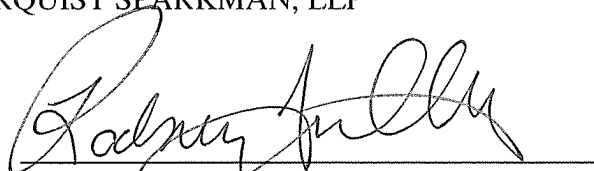
Applicants hereby submit that all claims are in condition for allowance and it is requested that the Examiner pass this case to issue. If the Examiner has any additional questions about the application, the Examiner is invited to call Applicants' attorney at the number listed below.

Respectfully submitted,

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